

**Complete Set of Claims**

1.(currently amended) A fine pattern forming material comprising a water-soluble resin, a water-soluble crosslinking agent, ~~and~~ a solvent consisting of water or a mixed solvent of water and a water-soluble organic solvent, ~~characterized in that the above fine pattern forming material comprises~~ and an amine compound which is at least one selected from the group ~~consisting~~ of a primary amine compound selected from a group of hydrazine, urea, amino acid, a glucosamine derivative and a polyallylamine derivative, where the ~~an~~ amino group of ~~which the polyallylamine~~ is partially protected at least by one selected from the group ~~consisting~~ of an alkylloxycarbonyl group, an aryloxycarbonyl group and an alkylcarbonyl group, and a quaternary amine compound ~~thereof consisting~~ selected from a group of dimethylammonium salt, trimethylammonium salt, tetramethylammonium salt, dimethylethylbenzylammonium salt and N-methylpyridinium salt and that pH value of the ~~above~~ fine pattern forming material exceeds 7.0.

2.(currently amended) The fine pattern forming material according to claim 1 wherein the ~~above~~ water-soluble resin is at least one selected from ~~the~~ a group ~~consisting~~ of a polyvinylalcohol derivative, a polyvinylpyrrolidone derivative and a polyacrylic acid derivative.

3.(currently amended) The fine pattern forming material according to claim 1 ~~or 2~~, wherein the above amine compound is a polyallylamine derivative having the molecular weight of 1,000 to 10,000.

4.(currently amended) The fine pattern forming material according to ~~any one of~~ claims 1 ~~to 3~~ further comprising a surfactant.

5.(currently amended) The fine pattern forming material according to claim 4, wherein the above surfactant is at least one selected from the group ~~consisting~~ of an anionic surfactant ~~consisting~~ selected from a group of alkylsulfonate, alkylbenzene sulfonic acid and alkylbenzenesulfonate, a cationic surfactant ~~consisting~~ selected from a group of laurylpyridinium chloride and laurylmethylammonium chloride and a nonionic surfactant ~~consisting~~ selected from a group of polyoxyethylene octylether, polyoxyethylene laurylether and polyoxyethylene acetylenic glycolether.

6.(currently amended) A fine pattern forming method ~~which is characterized in~~ comprising a step of forming a resist pattern made of a photoresist on a substrate, a step wherein a coating layer is formed by applying the fine pattern forming material ~~described in any one of claims 1 to 5~~ over the resist pattern, a step wherein the area neighboring to a the resist pattern is crosslinked and/or cured by heating the ~~before-described~~ resist pattern and the ~~before-described~~ coated layer and caused by a diffusion of an acid from the resist pattern, and a step wherein the ~~before-described~~ coated layer is developed by water or a mixture of water and a water-soluble organic solvent after heating.

7.(new) The fine pattern forming material according to claim 1 where water-soluble crosslinking agent is at least one selected from the group consisting of a melamine derivative and a urea derivative.

8.(new) The fine pattern forming material according to claim 1 where organic solvent is at least one selected from a group of alcohols, ketones, esters, ethylene glycol monoalkylethers, ethylene glycol monoalkylether acetates, propylene glycol monoalkylethers, propylene glycol monoalkylether acetates, lactic esters, aromatic hydrocarbons, amides, lactones, aprotic polar

Serial No.: To Be Assigned  
Filed: January 17, 2006

solvents.

9.(new) The fine pattern forming material according to claim 1, further comprising a plasticizer.

10.(new) The fine pattern forming material according to claim 4, further comprising a plasticizer.

11.(new) The method of claim 6, where the curing temperature is in the range of about 90°C to about 130°C.